

# Dialog DataStar



options

logoff

feedback

help

databases

easy  
search

## Advanced Search: INSPEC - 1969 to date (INZZ)

limit

### Search history:

No.	Database	Search term	Info added since	Results	
1	INZZ	planariz\$ OR polish\$ AND capacitor	unrestricted	2886	<a href="#">show titles</a>
2	INZZ	1 AND cmp	unrestricted	589	<a href="#">show titles</a>
3	INZZ	1 AND dram	unrestricted	106	<a href="#">show titles</a>
4	INZZ	1 AND trench ADJ capacitor	unrestricted	8	<a href="#">show titles</a>
5	INZZ	1 AND (via OR hole OR window OR opening)	unrestricted	431	<a href="#">show titles</a>

[hide history](#)
Enter your search term(s): [Search tips](#)
  

 Information added since:  or:    
 (YYYYMMDD)

Select special search terms from the following list(s):

poli- f.

L Number	Hits	Search Text	DB	Time stamp
1	28947	CAPACITOR AND (PLANAR\$ OR POLISH\$) AND (OPENING OR HOLE OR WINDOW OR CONTACT OR VIA)	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM TDB	2003/04/10 11:28
8	5898	(CAPACITOR AND (PLANAR\$ OR POLISH\$) AND (OPENING OR HOLE OR WINDOW OR CONTACT OR VIA)) AND (CMP OR (CHEMICAL ADJ MECHANICAL))	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM TDB	2003/04/10 11:29
15	3449	((CAPACITOR AND (PLANAR\$ OR POLISH\$) AND (OPENING OR HOLE OR WINDOW OR CONTACT OR VIA)) AND (CMP OR (CHEMICAL ADJ MECHANICAL))) AND DRAM	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM TDB	2003/04/10 11:31
22	19	((CAPACITOR AND (PLANAR\$ OR POLISH\$) AND (OPENING OR HOLE OR WINDOW OR CONTACT OR VIA)) AND (CMP OR (CHEMICAL ADJ MECHANICAL))) AND DRAM) AND @PY<1992	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM TDB	2003/04/10 11:35
29	24	((CAPACITOR AND (PLANAR\$ OR POLISH\$) AND (OPENING OR HOLE OR WINDOW OR CONTACT OR VIA)) AND (CMP OR (CHEMICAL ADJ MECHANICAL))) AND DRAM) AND @PY<1993	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM TDB	2003/04/10 11:35

L Number	Hits	Search Text	DB	Time stamp
1	591	((438/243) or (438/386)).CCLS.	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM TDB	2003/04/10 15:34
8	1422	(438/692).CCLS.	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM TDB	2003/04/10 15:27
15	955	(cmp or (chemical adj mechanical polishing)) and (trench adj capacitor)	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM TDB	2003/04/10 15:36
22	24	((cmp or (chemical adj mechanical polishing)) and (trench adj capacitor)) and @py<1993	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM TDB	2003/04/10 15:37